

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:	Confirmation No.: 5377
Makiko KITAZOE, et al	Art Unit: 1716
Application No.: 10/591,905	Examiner: Keath T. CHEN
Filed: November 6, 2006	Attorney Docket No.: 029567-00010
For: SELF-CLEANING CATALYTIC CHEMICAL VAPOR DEPOSITION APPARATUS AND CLEANING METHOD THEREOF	

RESPONSE UNDER 37 C.F.R. §1.116

MAIL STOP AF

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

January 12, 2012

Sir:

In response to the September 16, 2011, Office Action, which has been received and carefully noted, the following remarks are being submitted. Claims 1-3, 6-18, and 20 are pending, of which claims 10-18 are withdrawn. Reconsideration of the application is respectfully requested.

The Office Action rejects claims 1-3, 6-9, and 20 are rejected under 35 U.S.C. §103(a) as being obvious over Ishibashi (U.S. Patent No. 6,375,756) in view of Sawayama et al. (U.S. Patent Application Publication No. 2003/0164225), Dowling (U.S. Patent No. 6,562,201), Harris et al. (U.S. Patent No. 4,781,803) and Reale (U.S. Patent No. 5,451,754). Applicants respectfully traverse the rejection.

In particular, the current application claims a self-cleaning catalytic chemical vapor deposition apparatus for forming a thin film, including a reaction chamber